## **PROGRAM**

## Wednesday, April 26th, 2017

Session '	1	Introd	uction
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09:00	<b>Welcome</b> Matthias Petzold, Fraunhofer IMWS-CAM (DE)
09:20	Keynote 1 The 3D Technology Landscape: Expected Reliability Issues, Failure Mechanisms and Available Analysis Techniques Ingrid De Wolf, IMEC (BE)
10:00	<b>Keynote 2 Failure Analysis Challenges of Multi-Chip Modules</b> Jörg Krinke, Robert Bosch GmbH (DE)
10:40	Material Understanding Combined with Failure Analysis – A Prerequisite for a Successful System in Package Integration Klaus Pressel, Infineon AG (DE)
11:00	Magnetic Field Imaging in Current FA Landscape: 3D Fault Isolation, LIT and EOTPR Techniques Comparison Antonio Orozco, Neocera LLC (US)
11:20	Lunch Break / Exhibition Opening
	Session 2 Defect Localization
13:00	3D Thermal Defect Localization by Time-resolved Temperature Response Signal Processing Frank Altmann, Fraunhofer IMWS-CAM (DE)
13:20	Light-Induced Capacitance Alteration for Non-Destructive Open Failure Localization in 3-D TSV Structures Kristof J.P. Jacobs, IMEC (BE)
13:40	Scanning Photoacoustic GHz-Microscopy for the Application in Microelectronics Failure Analysis and Metrology Sebastian Brand, Fraunhofer IMWS-CAM (DE)
14:00	<b>Exploring the limits of Spatial OBIRCH &amp; LIT Resolution in 28nn</b> Pascal Limbecker, GLOBALFOUNDRIES Inc. (DE)
14:20	Electrical Failure Analysis in SEM: Developments in Techniques and Applications Grigore Moldovan, point electronic GmbH (DE)
14:40	Coffee Break / Exhibition

Session	3 9	Samp	le Pre	paration

15:20	A Pico-Second Laser Tool for Fast, Large Cross Section ROI' of Packages and Devices Mike Hassel Shearer, Gatan Inc. (US)
15:40	Latest Results on Gas Injection System for Failure Analysis Applications Grégory Goupil, Orsay Physics-Tescan Orsay Holding (FR)
16:00	Sample Preparation Tricks for Correlative FIB TOF-SIMS and Computed X-ray Nanotomography Guillaume Audoit, CEA-Leti (FR)
16:20	Microwave Induced Plasma Decapsulation of System in Package Devices Jiaqi Tang, JIACO Instruments B.V. (NL)
16:40	Circuit Edit on Package Level

- Christian Hollerith, Infineon AG (DE)

  17:00 Drinks Reception / Exhibition
- 19:00 Dinner "25 Year Anniversary of microelectronics research in Halle (Saale)", Steintor Varieté, Am Steintor 10, 06112 Halle

## Thursday, April 27th, 2017

12:50 Lunch Break / Exhibition

14:00 **Lab-Tours** 

	Session 4 Physical Failure Analysis
08:30	Calibrated Capacitive Imaging for Dopant Type Determination Sören Hommel, Infineon AG (DE)
08:50	<b>Dopant Imaging for Wide Band Gap Materials (SiC, GaN)</b> Maher Nafouti, Université de Tours (FR)
09:10	High Resolution Cathodoluminescence for Characterization of Electronic Materials and Devices  Marcin Zielinski, Attolight AG (CH)
09:30	Chemical Imaging by Photo-induced Forces - Fundamentals and Applications of an Emerging Technology  Derek Nowak, Molecular Vista (US)
09:50	Non Invasive Lab Tool for Micron Level Trace Element Mapping & Contamination Analysis in FA & Process Control with Capabilities Comparable to Synchrotron Based microXRF S. H. Lau, Sigray Inc. (US)
10:10	FIB TOF-SIMS Crater Wall Analysis and Tomography Felix Kollmer, Ion-Tof GmbH (DE)
10:30	Coffee Break / Exhibition
	<b>Session 5 Material Characterization and Mechanical Testing</b>
11:10	IR Transient Temperature Measurement and Thermo Reflectance Mapping on GaN HEMTs in 2,5D Package Dominique Carisetti, Thales Group (FR)
11:30	Chip Package Interaction - BABSI Test with Live Electrical Test Monitoring Holm Geisler, GLOBALFOUNDRIES Inc (DE)
11:50	Gas Analysis in Closed MEMS Cavitites using Confocal Micro Raman Spectroscopy Norbert Söllner, Infineon AG (DE)
12:10	Polariscopy for Stress Measurements Martin Herms, PVA TePla AG (DE)
12:30	Investigating Stress Measurement Capabilities of GHz Scanning Acoustic Microscopy for 3D Failure Analysis Ahmad Khaled, IMEC (BE)